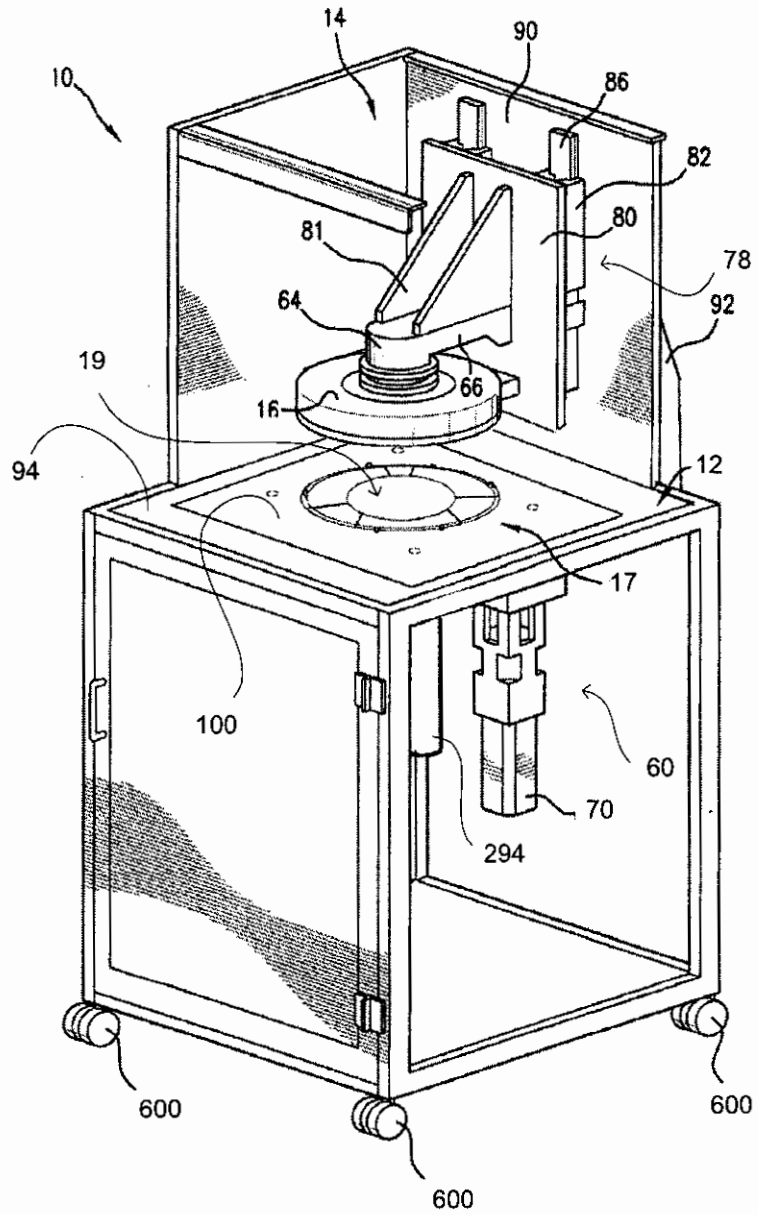

14
90
10
86
82
80
81
78
64
92
19
66
16
94
12
17
100
60
70
294
600
600
600

FIG. 1

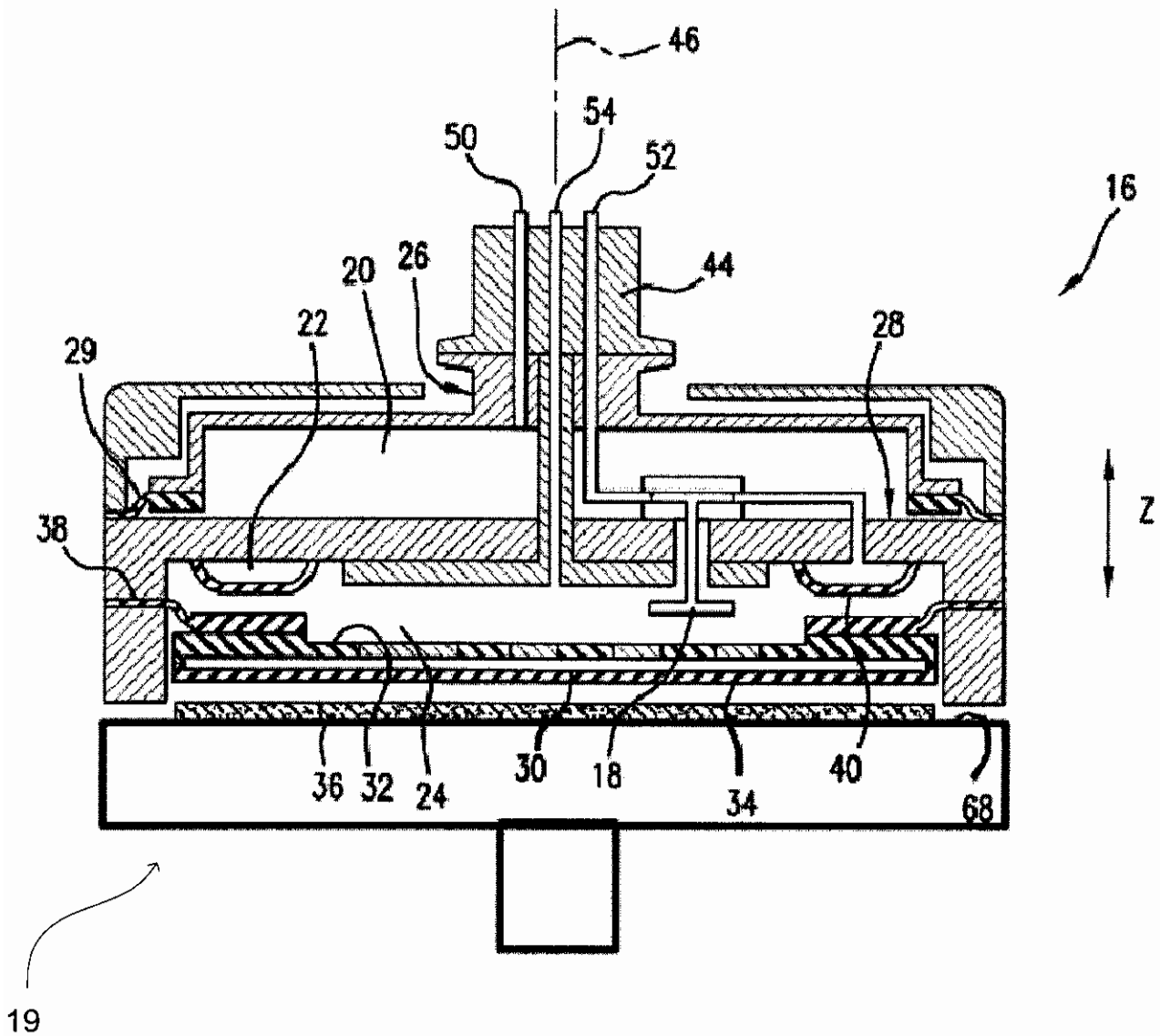


FIG. 2

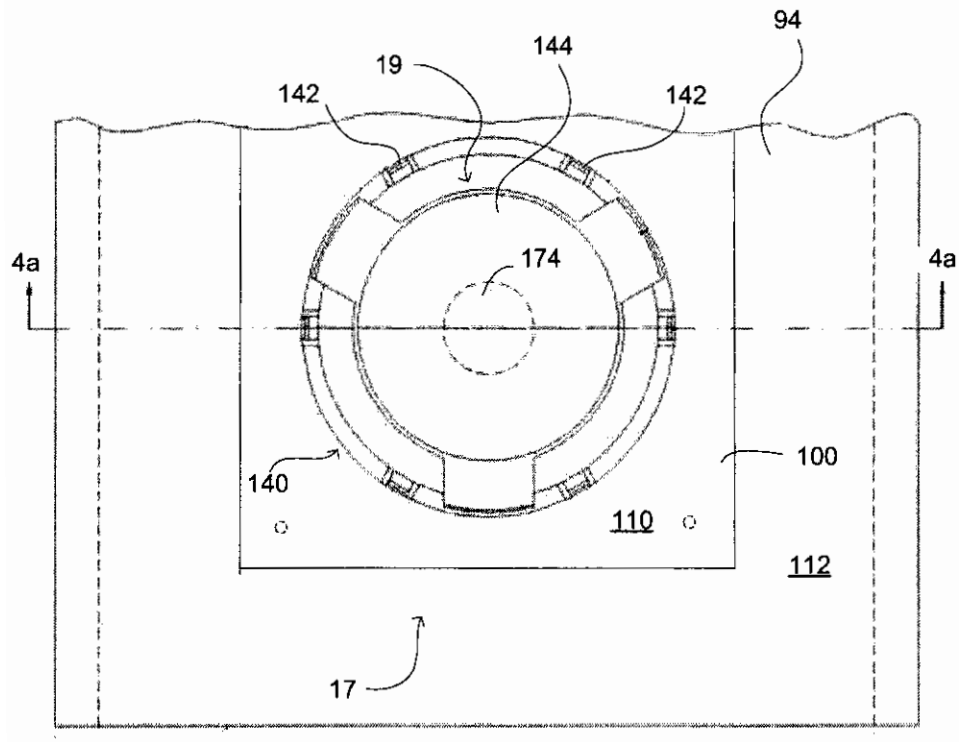

94
144
19
142
142
4a
4a
174
140
100
110
112
17

FIG. 3

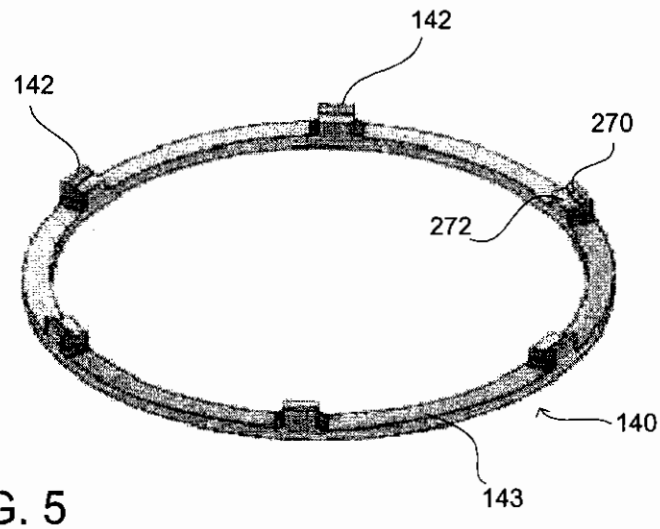

142
142
270
272
140
143

FIG. 5

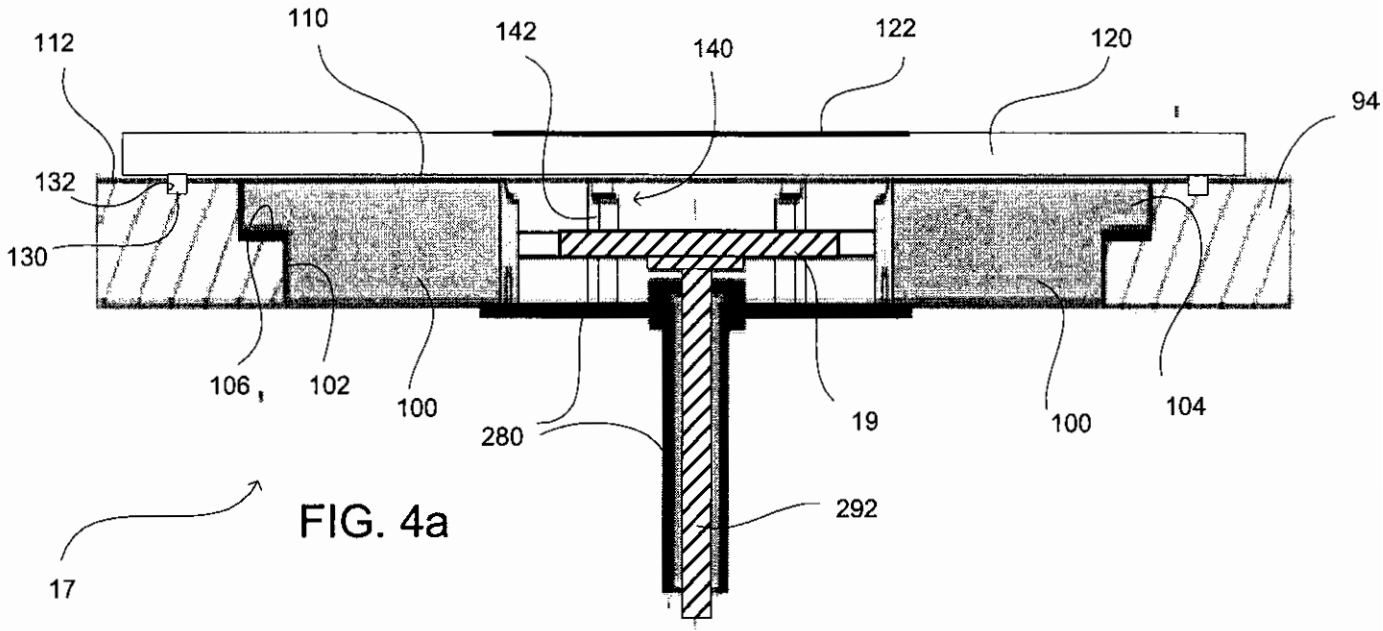

112
110
142
140
122
120
94
132
130
106
102
100
280
19
100
104
292
17

FIG. 4a

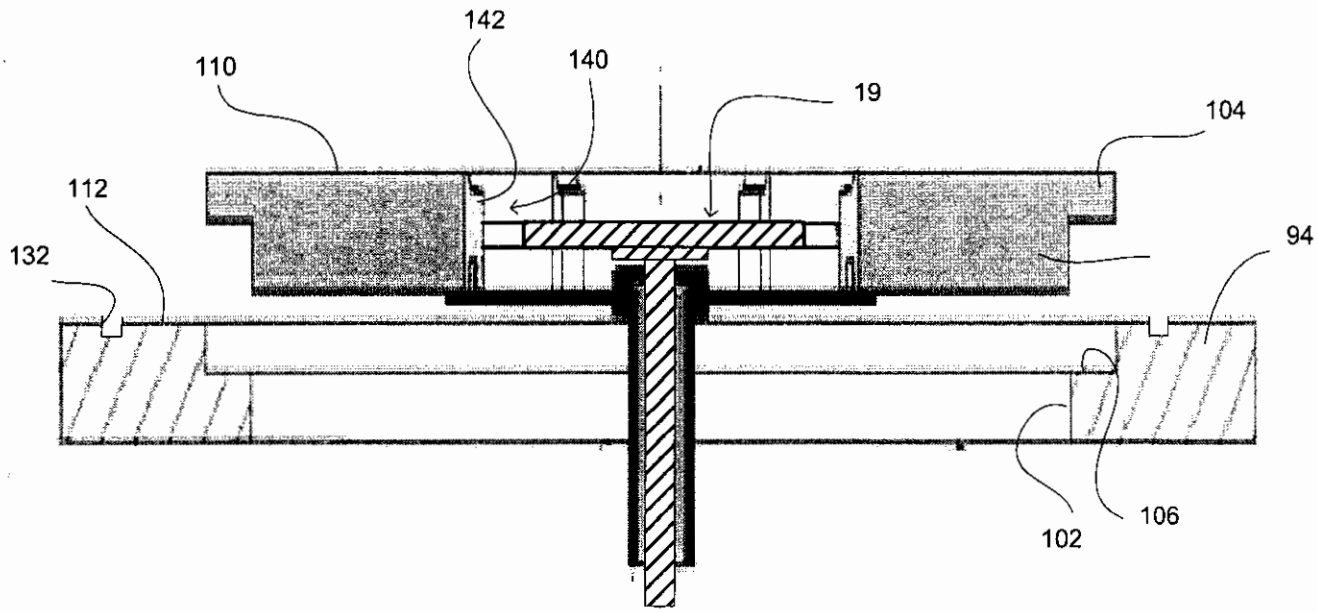

142
140
110
19
104
112
132
94
102
106

FIG. 4b

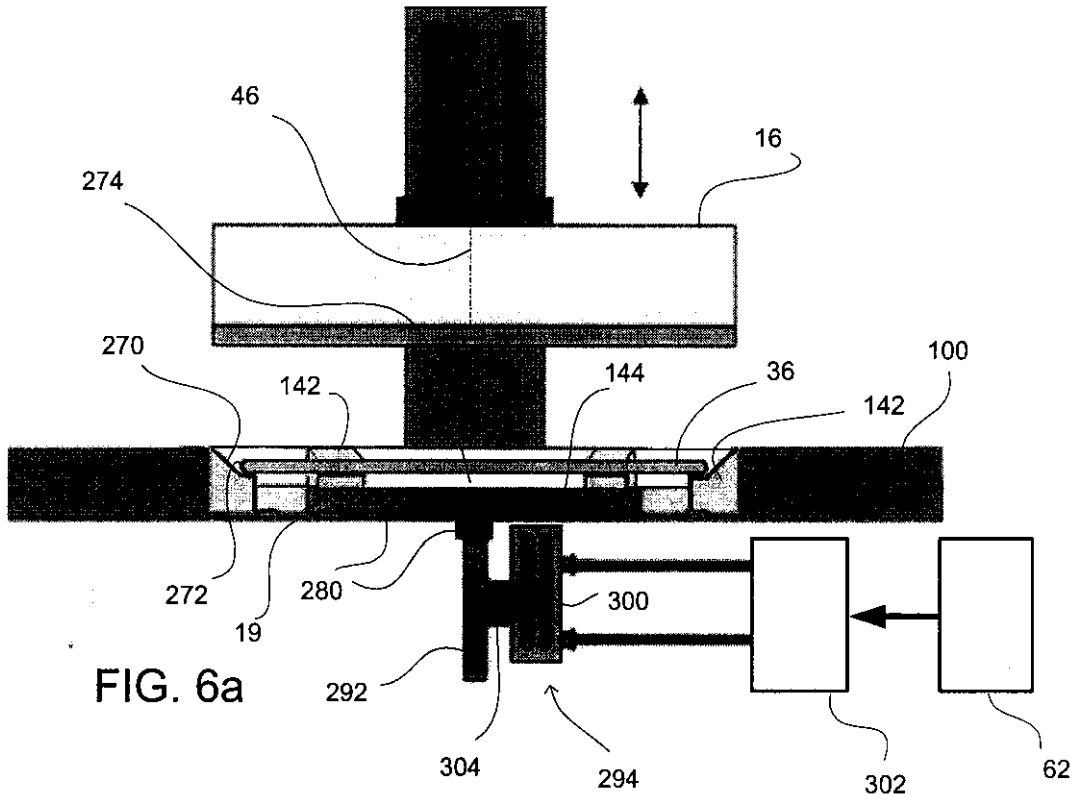

46
16
274
270
142
144
36
142
100
272
280
19
300
292
304
294
302
62

FIG. 6a

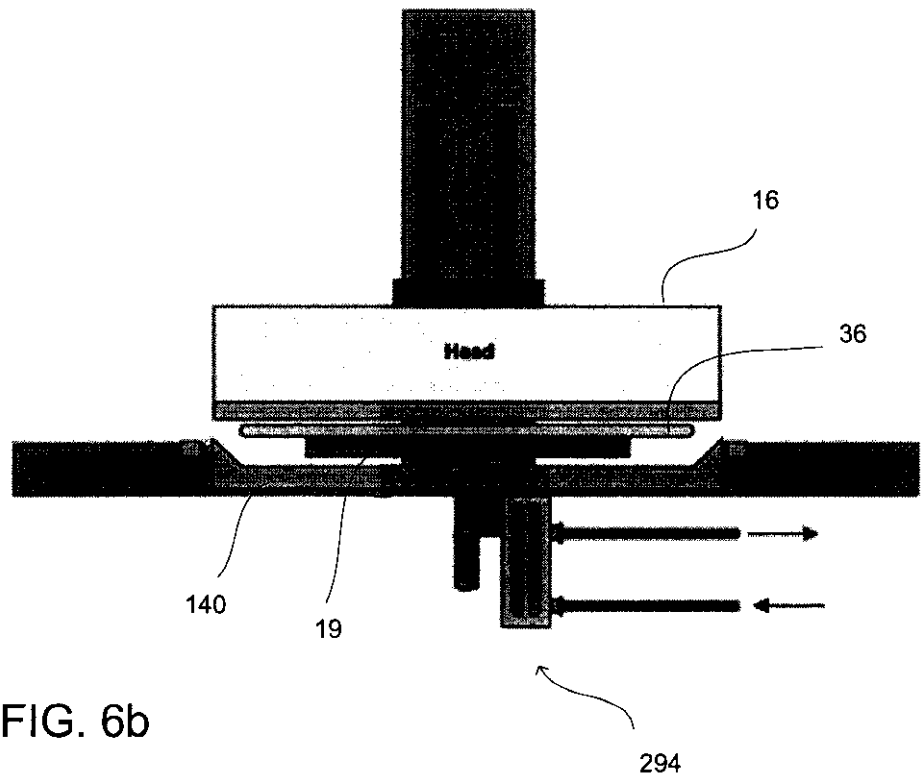

16
Head
36
140
19
294

FIG. 6b

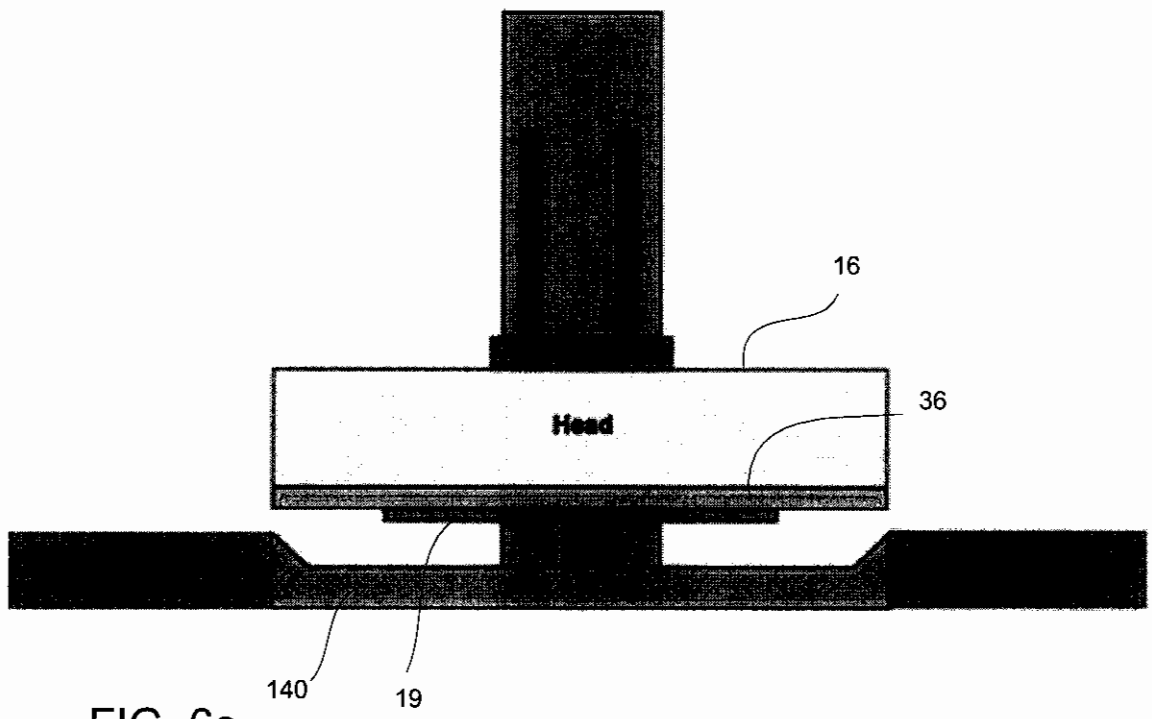


FIG. 6c

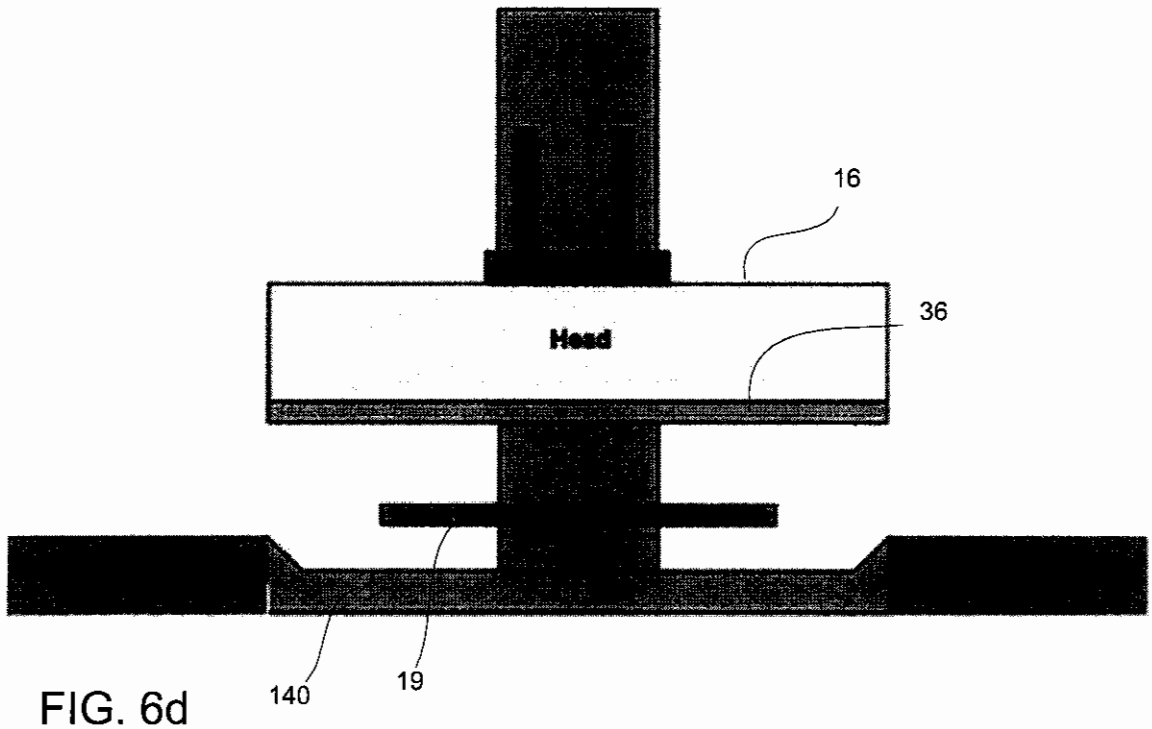


FIG. 6d

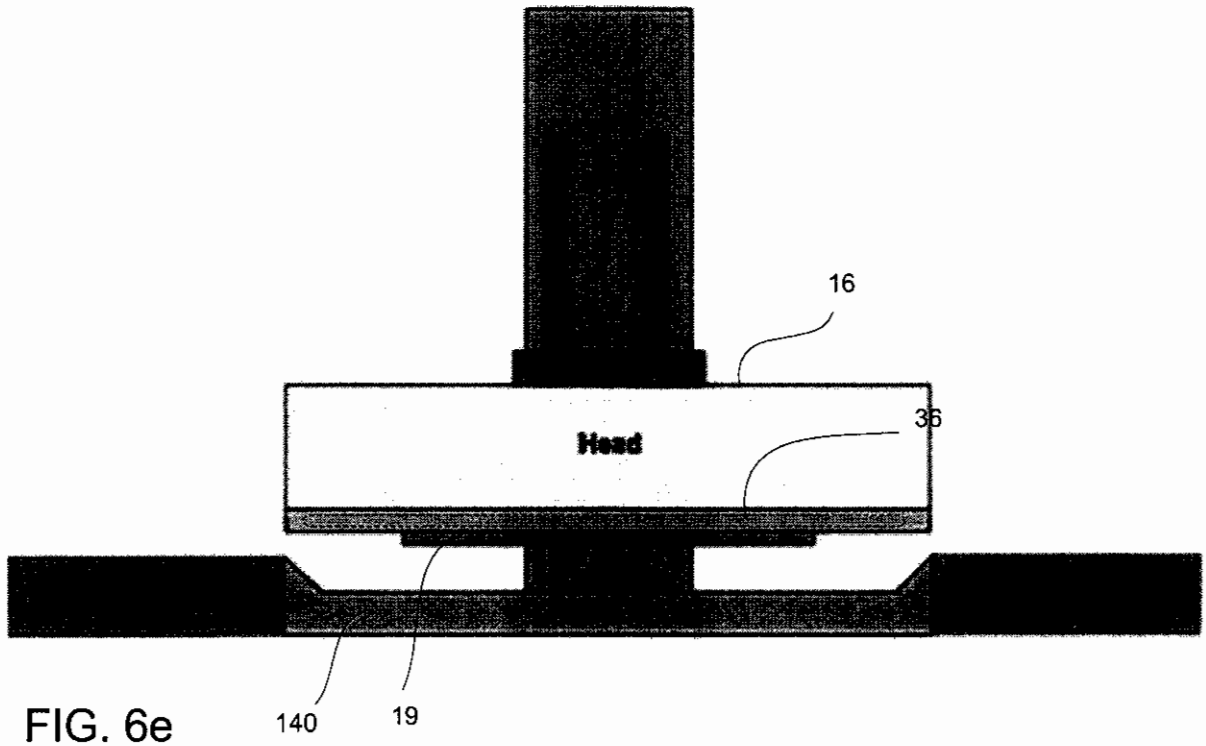


FIG. 6e

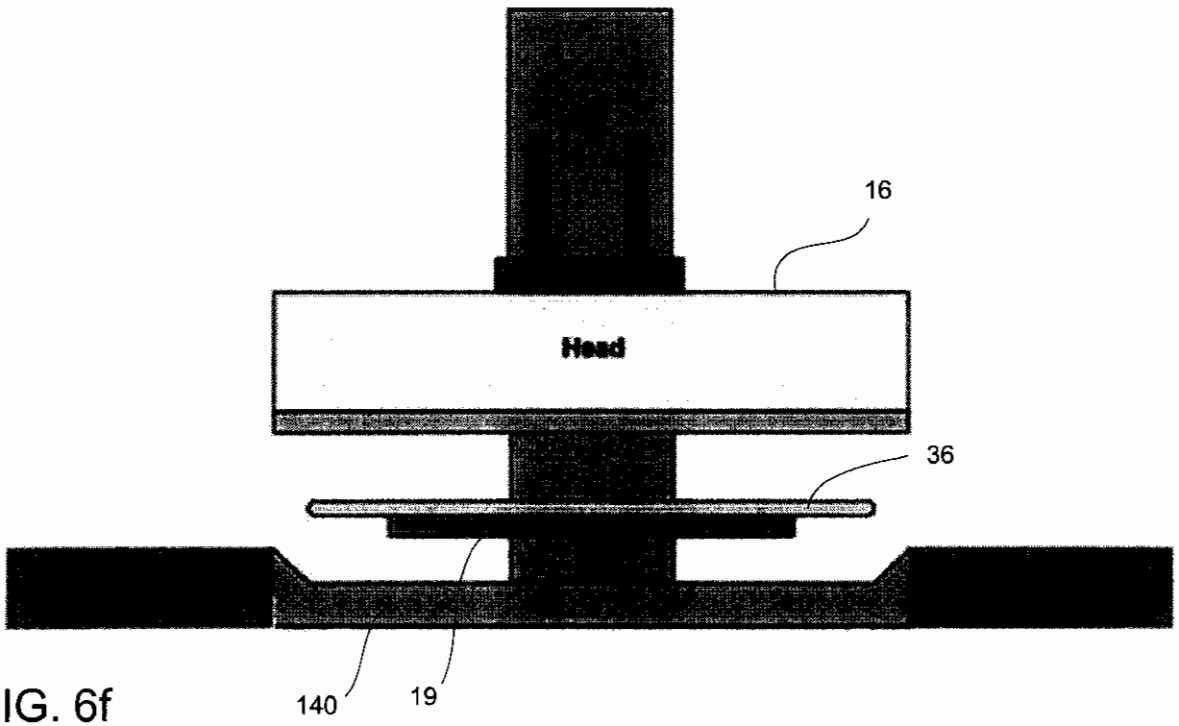


FIG. 6f

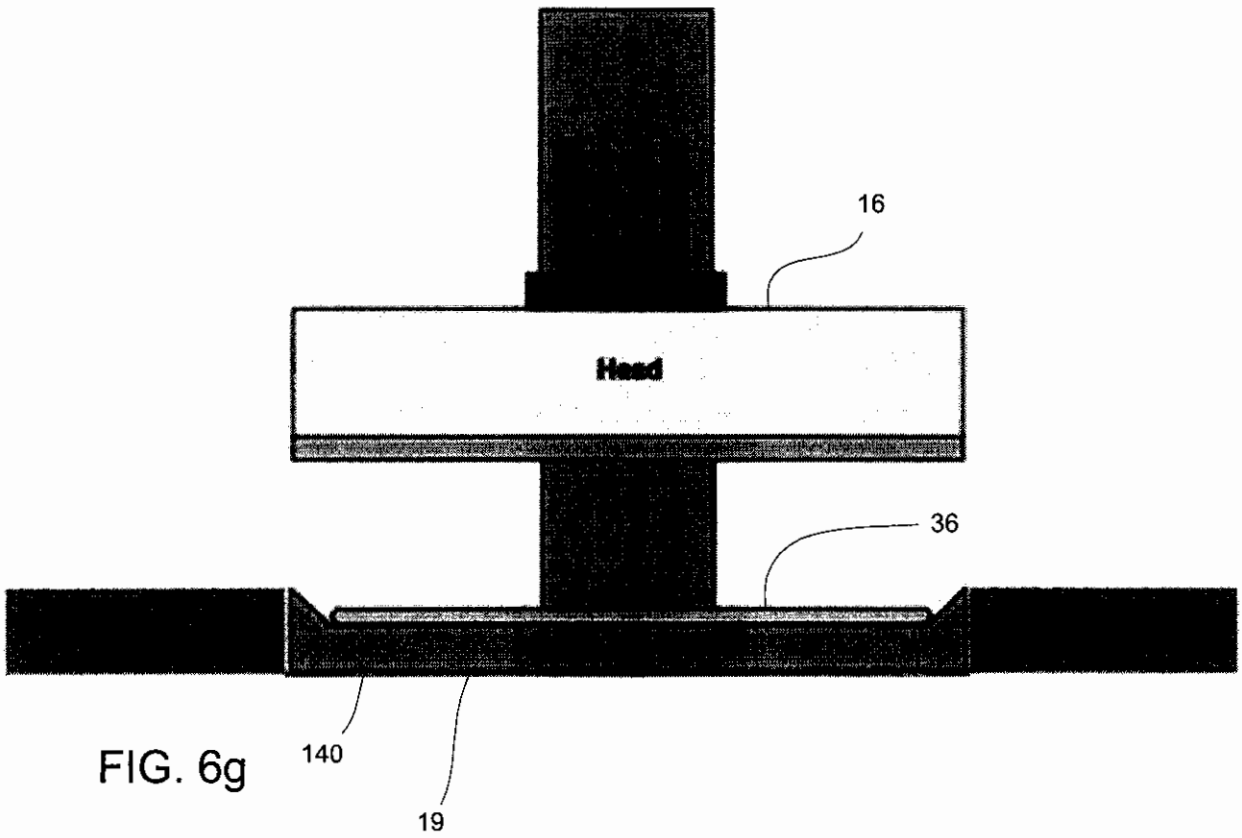


FIG. 6g

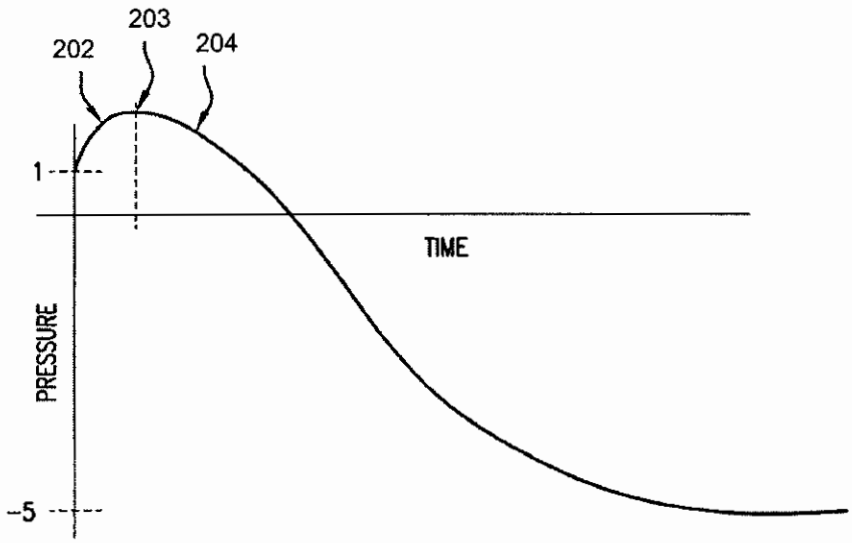


FIG. 8

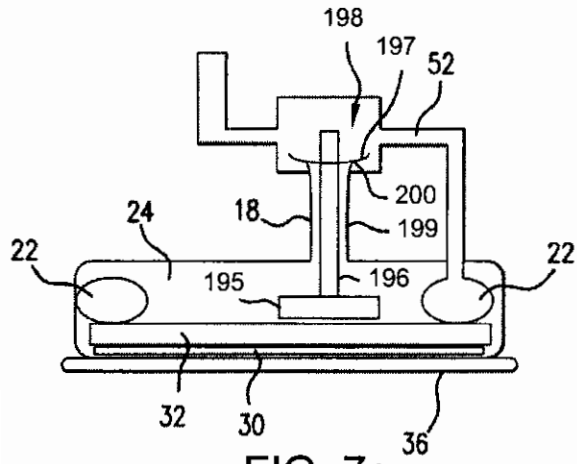

198
197
52
200
18
24
199
22
22
195
196
32
30
36

FIG. 7a

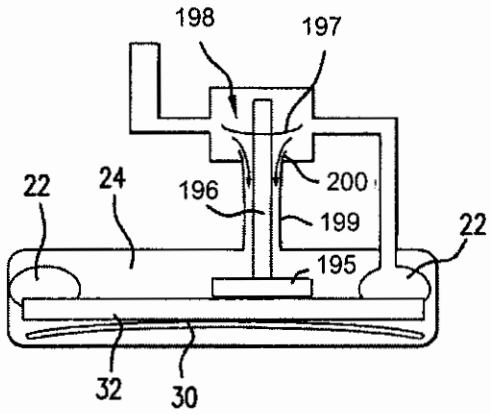

198
197
22
24
196
200
199
22
195
32
30

FIG. 7b

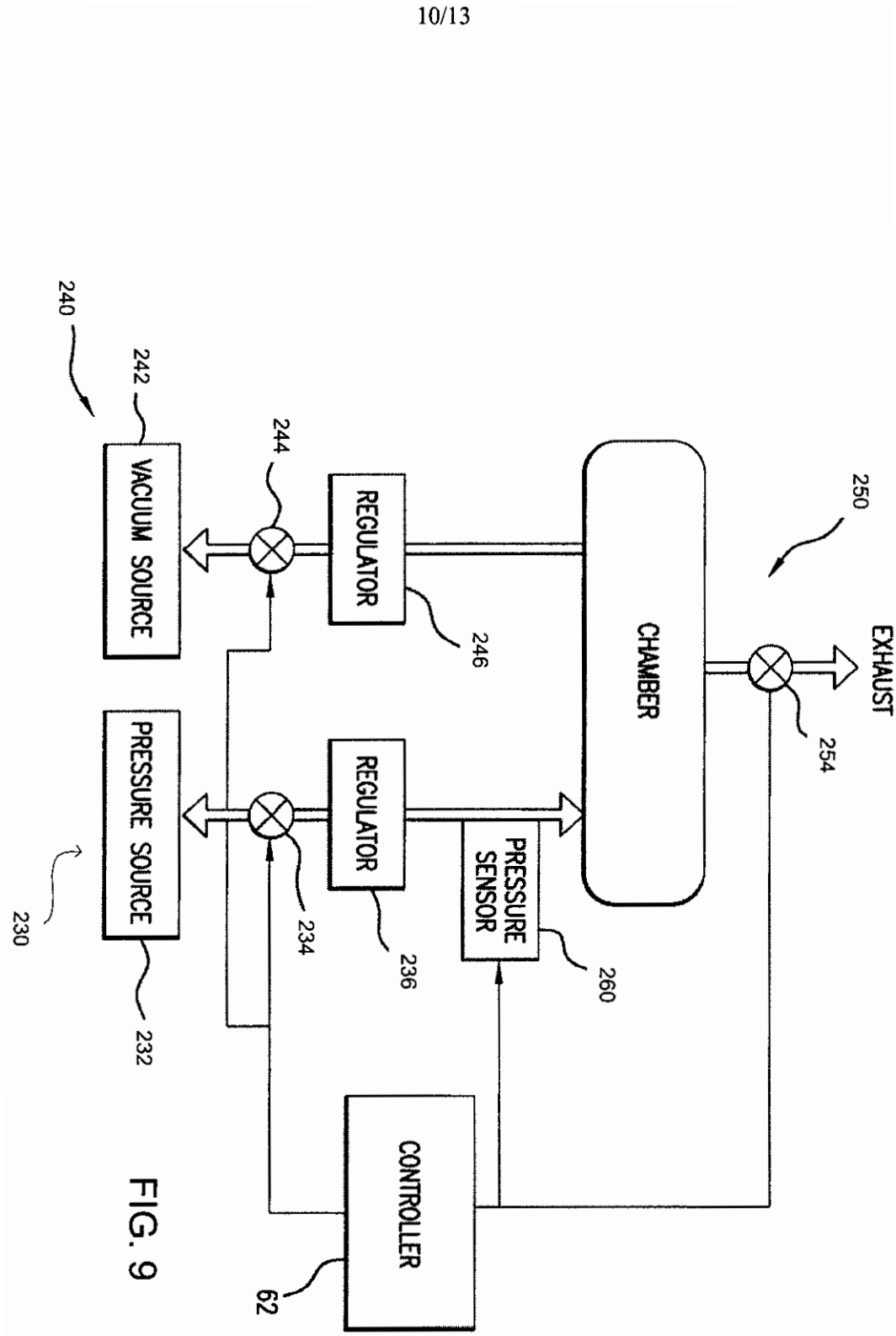

240
242
VACUUM SOURCE
244
REGULATOR
246
250
CHAMBER
EXHAUST
254
230
PRESSURE SOURCE
232
234
REGULATOR
236
PRESSURE SENSOR
260
CONTROLLER
62

FIG. 9

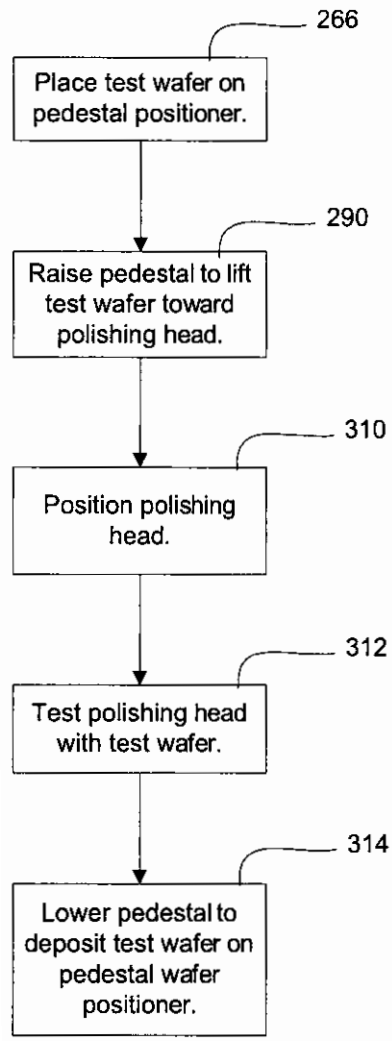

266
Place test wafer on pedestal positioner.
290
Raise pedestal to lift test wafer toward polishing head.
310
Position polishing head.
312
Test polishing head with test wafer.
314
Lower pedestal to deposit test wafer on pedestal wafer positioner.

FIG. 10

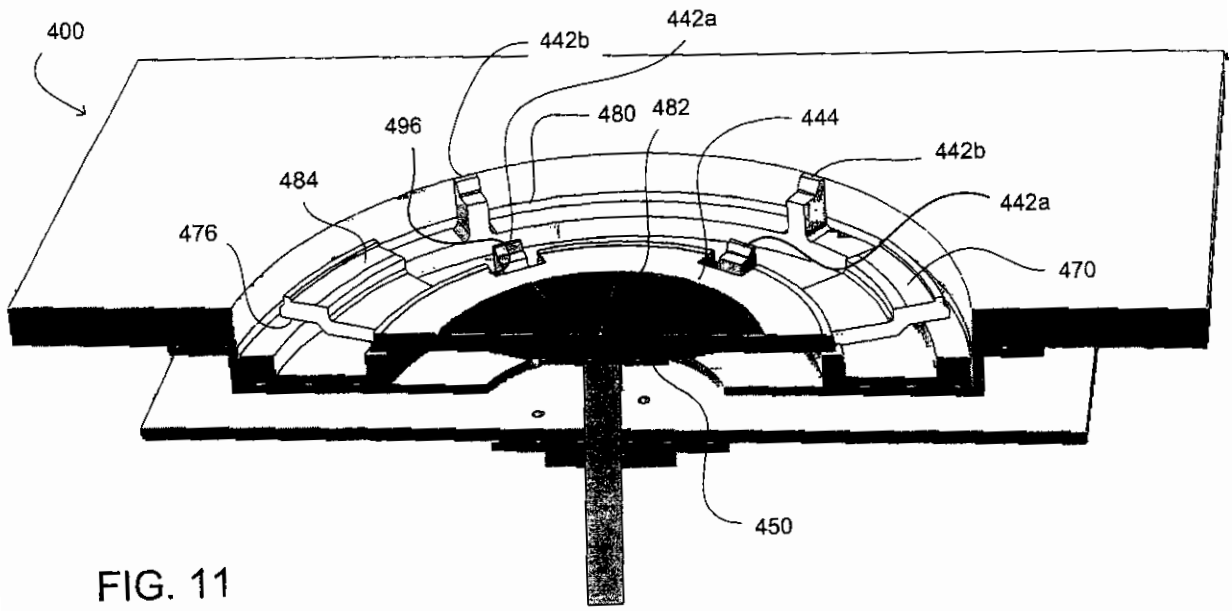

400
442b
442a
480
482
444
496
442b
484
442a
476
470
450

FIG. 11

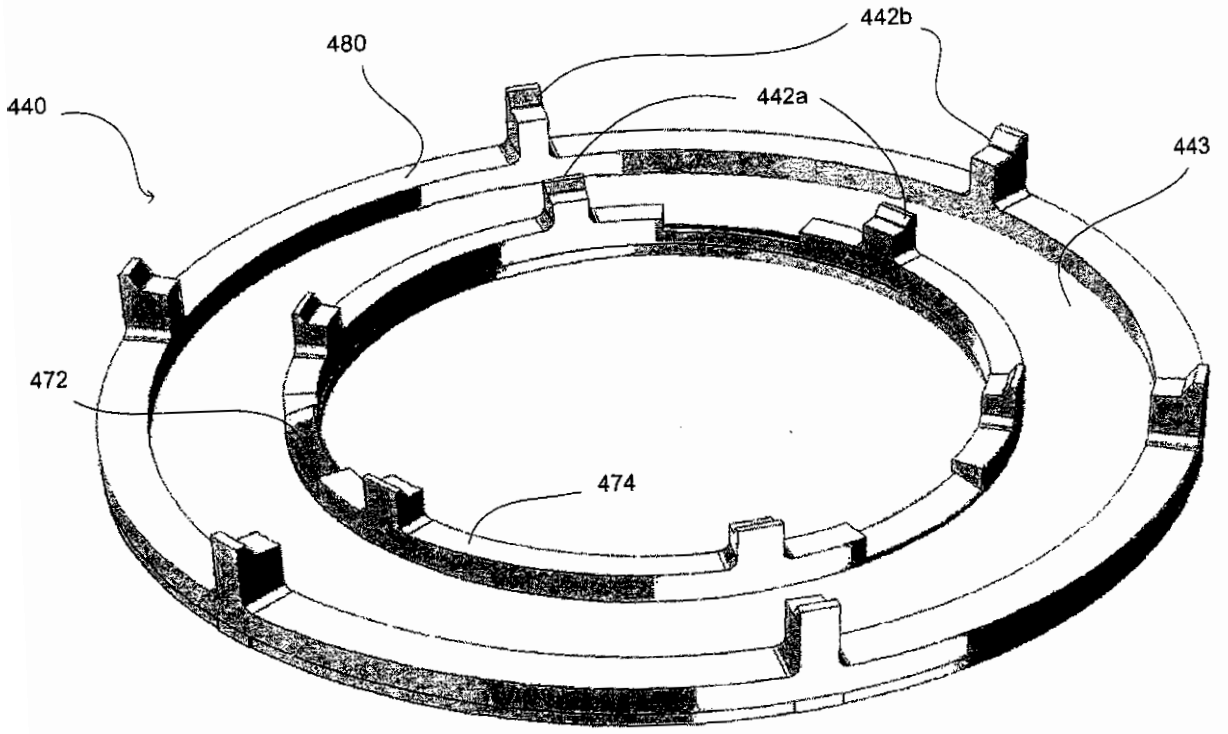

442b
480
442a
440
443
472
474

FIG. 12

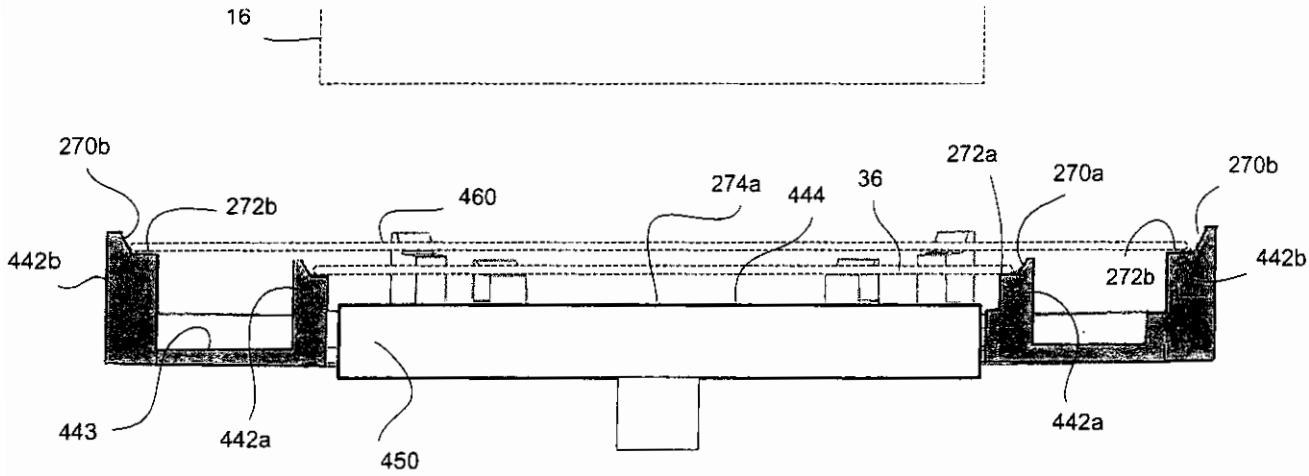

16
270b
272b
460
274a
444
36
272a
270a
270b
442b
272b
442b
443
442a
450
442a

FIG. 13

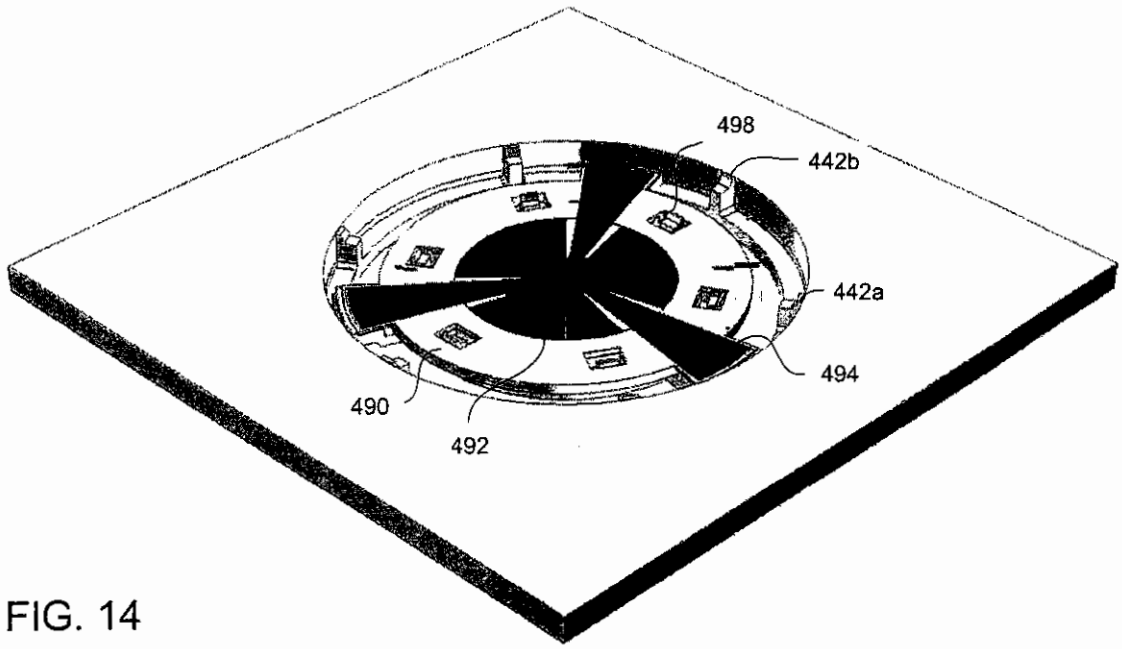

498
442b
442a
494
490
492

FIG. 14